L Number	Hits	Search Text	DB	Time stamp
- Mariner	4	"200012465"	EPO; JPO;	2003/11/04 10:06
	_		DERWENT	
-	11	"12465"	EPO; JPO; DERWENT	2003/11/03 13:00
-	0	"P200012465"	EPO; JPO; DERWENT	2003/11/03 13:01
-	2	"09237927"	EPO; JPO; DERWENT	2003/11/03 13:01
-	2	5866471.pn.	EPO; JPO; DERWENT	2003/11/04 08:28
-	1	5866471.pn.	USPAT; US-PGPUB	2003/11/04 08:28
_	30	(Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or	USPAT; US-PGPUB; EPO; JPO;	2004/04/22 13:52
		Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2	DERWENT; IBM_TDB	
-	19	cyclopentasilane)) "59015"	EPO; JPO; DERWENT;	2003/11/04 10:29
-	2	"200059015"	IBM_TDB EPO; JPO; DERWENT; IBM TDB	2003/11/04 10:29
_	2	"200059044"	EPO; JPO; DERWENT; IBM TDB	2003/11/04 11:08
_	1420	(427/552,553,555,558).CCLS.	USPAT; US-PGPUB	2004/04/22 15:34
-	1056	(427/226).CCLS.	USPAT; US-PGPUB	2003/11/04 11:09
_	2229	((427/248.1,255.18,255.23) or (438/503,507)).CCLS.	USPAT; US-PGPUB	2004/04/22 15:35
_	2859	(427/258,259,261,264,265,270,271).CCLS.	USPAT; US-PGPUB	2004/04/22 15:35
_	417	(423/348,349).CCLS.	USPAT; US-PGPUB	2004/04/22 15:35
_	519	(117/88,95).CCLS.	USPAT; US-PGPUB	2004/04/22 15:35
-	8126	((427/552,553,555,558).CCLS.) ((427/226).CCLS.) (((427/248.1,255.18,255.23) or	USPAT; US-PGPUB	2004/04/23 09:14
_ 0	14	(438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.)	USPAT; US-PGPUB	2004/04/22 15:37
		((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.)) and ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))		

		· · · · · · · · · · · · · · · · · · ·		
	3	(((427/552,553,555,558).CCLS.) or ((427/258,259,261,264,265,270,271).CCLS.)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12	USPAT; US-PGPUB	2004/04/22 15:39
		or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))		
-	32	1	USPAT; US-PGPUB	2004/04/22 15:40
	15	((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.)) and (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5)) with (select\$7 or pattern\$3 or nonuniform or (non adj uniform))) and ((monolayer or (mono adj layer) or fluoroalkyl or fluorine or SAM or (self adj assembl\$3) or fluoro\$12) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or	USPAT; US-PGPUB	2004/04/22 15:40
_	694	deactiv\$5 or (de adj activ\$5))) (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5)) with (select\$7 or pattern\$3 or nonuniform or (non adj uniform))) and ((monolayer or (mono adj layer) or fluoroalkyl or fluorine or SAM or (self adj assembl\$3) or fluoro\$12) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5)))	USPAT; US-PGPUB	2003/11/04 11:32
-	59		USPAT; US-PGPUB	2003/11/04 12:54
	53	(((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5)) with (select\$7 or pattern\$3 or nonuniform or (non adj uniform))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5))) not (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.)) and (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5)) with (select\$7 or pattern\$3 or nonuniform or (non adj uniform)) and ((monolayer or (mono adj layer) or fluoroalkyl or fluorine or SAM or (self adj assembl\$3) or fluoro\$12) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or	USPAT; US-PGPUB	2003/11/04 11:33
		deactiv\$5 or (de adj activ\$5))))		

-	2	(((silicon or Si) near2 (coat\$3 or film or	EPO; JPO;	2003/11/04 11:39
		layer or deposit\$3 or \$4CVD or vaporiz\$5))	DERWENT;	
Ì		with (select\$7 or pattern\$3 or nonuniform	IBM_TDB	
		or (non adj uniform))) and ((monolayer or		
		(mono adj layer) or SAM or (self adj		
		assembl\$3)) with (mask\$3 or inactiv\$5 or		
1		(in adj activ\$5) or deactiv\$5 or (de adj		
	_	activ\$5)))		İ
-	7	(((silicon or Si) near2 (coat\$3 or film or	EPO; JPO;	2003/11/04 11:42
		layer or deposit\$3 or \$4CVD or	DERWENT;	
		vaporiz\$5))) and ((monolayer or (mono adj	IBM_TDB	
		layer) or SAM or (self adj assembl\$3))		
		with (mask\$3 or inactiv\$5 or (in adj		
		activ\$5) or deactiv\$5 or (de adj activ\$5)		
	1.55	or pattern\$3))		
-	466	(((silicon or Si) near2 (coat\$3 or film or	USPAT;	2003/11/04 11:43
		layer or deposit\$3 or \$4CVD or	US-PGPUB	
		vaporiz\$5))) and ((monolayer or (mono adj		
		layer) or SAM or (self adj assembl\$3))		
		with (mask\$3 or inactiv\$5 or (in adj		
		activ\$5) or deactiv\$5 or (de adj activ\$5)		
		or pattern\$3))		
-	27	((((silicon or Si) near2 (coat\$3 or film	USPAT;	2003/11/04 11:53
		or layer or deposit\$3 or \$4CVD or	US-PGPUB	
		vaporiz\$5))) and ((monolayer or (mono adj		
]	layer) or SAM or (self adj assembl\$3))		
	Ì	with (mask\$3 or inactiv\$5 or (in adj		
		activ\$5) or deactiv\$5 or (de adj activ\$5)		
		or pattern\$3))) and		
		(((427/552,553,555,558).CCLS.)		
		((427/226).CCLS.)		
•		(((427/248.1,255.18,255.23) or		
		(438/503,507)).CCLS.)		
		((427/258,259,261,264,265,270,271).CCLS.)	!	
l _	1	((423/348,349).CCLS.) ((117/88,95).CCLS.))		
-	1	((tridecafluoro near3 triethoxysilane) or	USPAT;	2003/11/04 11:57
		FAS13 or ("FAS 13")) same (monolayer or	US-PGPUB	
		(mono adj layer) or SAM or (self adj		
		assembl\$5) or pattern or mask\$3 or		
ļ		<pre>inactiv\$5 or (in adj activ\$5') or (de adj activ\$5) or deactiv\$5)</pre>		
_	1	((tridecafluoro near5 triethoxysilane) or	ticpam.	2002/11/04 11 7-
		FAS13 or ("FAS 13")) same (monolayer or	USPAT;	2003/11/04 11:57
		(mono adj layer) or SAM or (self adj	US-PGPUB	
		assembl\$5) or pattern or mask\$3 or		
		inactiv\$5 or (in adj activ\$5) or (de adj		
		activ\$5) or deactiv\$5)		
_	60	((tridecafluoro near5 triethoxysilane) or	USPAT;	2003/11/04 12:07
		FAS13 or ("FAS 13")) and (monolayer or	US-PGPUB	2003/11/04 12:0/
		(mono adj layer) or SAM or (self adj	OD FREAD	
		assembl\$5) or pattern or mask\$3 or	i	
		inactiv\$5 or (in adj activ\$5) or (de adj		
		activ\$5) or deactiv\$5)		
-	4	(((tridecafluoro near5 triethoxysilane) or	USPAT;	2003/11/04 11:58
	-	FAS13 or ("FAS 13")) and (monolayer or	US-PGPUB	2003/11/04 11:38
		(mono adj layer) or SAM or (self adj	22 13100	
		assembl\$5) or pattern or mask\$3 or		
		inactiv\$5 or (in adj activ\$5) or (de adj		
		activ\$5) or deactiv\$5)) and	İ	
		(((427/552,553,555,558).CCLS.)		
ĺ		((427/226).CCLS.)		
		(((427/248.1,255.18,255.23) or		
		(438/503,507)).CCLS.)		
ĺ	}	((427/258, 259, 261, 264, 265, 270, 271).CCLS.)		
		((423/348,349).CCLS.) ((117/88,95).CCLS.))		
		,, = , = , = , = 0000.//		

-	56	(((tridecafluoro near5 triethoxysilane) or	USPAT;	2003/11/04 12:01
		FAS13 or ("FAS 13")) and (monolayer or	US-PGPUB	
		(mono adj layer) or SAM or (self adj		
		assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj		
	}	activ\$5) or deactiv\$5)) not		
		((((tridecafluoro near5 triethoxysilane)		
		or FAS13 or ("FAS 13")) and (monolayer or		
		(mono adj layer) or SAM or (self adj]
		assembl\$5) or pattern or mask\$3 or		
		inactiv\$5 or (in adj activ\$5) or (de adj		
		activ\$5) or deactiv\$5)) and		l
		(((427/552,553,555,558).CCLS.)		
		((427/226).CCLS.)		
		(((427/248.1,255.18,255.23) or		
		(438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)		
		((427/238,239,261,264,263,270,271).ccis.)		1
		((117/88,95).CCLS.)))		
_	0	((tridecafluoro near5 triethoxysilane) or	EPO; JPO;	2003/11/04 12:49
		FAS13 or ("FAS 13")) and (monolayer or	DERWENT;	
		(mono adj layer) or SAM or (self adj	IBM TDB	į
		assembl\$5) or pattern or mask\$3 or	_	<u> </u>
		inactiv\$5 or (in adj activ\$5) or (de adj		
	1	activ\$5) or deactiv\$5)		0000 /11 /01
-	4	Meeks.xp,xa. and (self adj assemb\$8)	USPAT;	2003/11/04 12:51
	46600	//Ci on cilicon) with /+62	US-PGPUB	2002/11/04 12:50
_	46692	((Si or silicon) with (coat\$3 or film or layer or deposit\$3 or \$4CVD) with	USPAT; US-PGPUB	2003/11/04 12:59
		(pattern\$3 or nonuniform\$3 or (non adj	US-FGFUB	
		uniform\$3) or mask\$3))		
_	573	(((Si or silicon) with (coat\$3 or film or	USPAT;	2003/11/04 12:54
		layer or deposit\$3 or \$4CVD) with	US-PGPUB	
		(pattern\$3 or nonuniform\$3 or (non adj		
		uniform\$3) or mask\$3))) and		<u> </u>
		(((427/552,553,555,558).CCLS.)		1
		((427/226).CCLS.)		
		(((427/248.1,255.18,255.23) or		
		(438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)	j	
		((423/348,349).CCLS.) ((117/88,95).CCLS.))		
_	422	((((Si or silicon) with (coat\$3 or film or	USPAT;	2003/11/04 13:52
İ		layer or deposit\$3 or \$4CVD) with	US-PGPUB	
		(pattern\$3 or nonuniform\$3 or (non adj		i i
		uniform\$3) or mask\$3))) and		
		(((427/552,553,555,558).CCLS.)		
		((427/226).CCLS.)		
1		(((427/248.1,255.18,255.23) or		
		(438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)		·
		((423/348,349).CCLS.)		
		((117/88,95).CCLS.))) and ((monolayer or		1
	1	(mono adj layer) or SAM or (self adj		
		assembl\$3)) or (mask\$3 or inactiv\$5 or (in		
	-	adj activ\$5) or deactiv\$5 or (de adj		
		activ\$5)))		
-	31013	(((Si or silicon) with (coat\$3 or film or	USPAT;	2003/11/04 12:57
		layer or deposit\$3 or \$4CVD) with	US-PGPUB	
		<pre>(pattern\$3 or nonuniform\$3 or (non adj uniform\$3) or mask\$3))) same ((monolayer</pre>		
		or (mono adj layer) or SAM or (self adj		
		assembl\$3)) or (mask\$3 or inactiv\$5 or (in		
		adj activ\$5) or deactiv\$5 or (de adj		
		activ\$5)))		
-	398	(((Si or silicon) with (coat\$3 or film or	USPAT;	2003/11/04 12:57
		layer or deposit\$3 or \$4CVD) with	US-PGPUB	
		(pattern\$3 or nonuniform\$3 or (non adj		
		uniform\$3) or mask\$3))) same ((monolayer		
		or (mono adj layer) or SAM or (self adj assembl\$3)) or (inactiv\$5 or (in adj		
		activ\$5) or deactiv\$5 or (de adj		
		activ(5)))		
	L		l	1

	5	(///Ci or cilican) with /costco on film and	Lugnam	10000/11/04 10 55
-	3	((((Si or silicon) with (coat\$3 or film or layer or deposit\$3 or \$4CVD) with	USPAT; US-PGPUB	2003/11/04 12:57
		(pattern\$3 or nonuniform\$3 or (non adj	US-PGPUB	
		uniform\$3) or mask\$3))) same ((monolayer		
		or (mono adj layer) or SAM or (self adj		
ļ		assembl\$3)) or (inactiv\$5 or (in adj		
1	1	activ\$5) or deactiv\$5 or (de adj	ļ	
		activ\$5)))) and		
		(((427/552,553,555,558).CCLS.)		
		((427/226).CCLS.)		
1	1	(((427/248.1,255.18,255.23) or		
		(438/503,507)).CCLS.)		
		((427/258,259,261,264,265,270,271).CCLS.)		
		((423/348,349).CCLS.) ((117/88,95).CCLS.))		
_	13228	((Si or silicon) adj (coat\$3 or film or	USPAT;	2003/11/04 13:02
		layer or deposit\$3 or \$4CVD) with	US-PGPUB	
	1	(pattern\$3 or nonuniform\$3 or (non adj		
	170	uniform\$3) or selecti\$6))		
_	170		USPAT;	2003/11/04 13:01
		layer or deposit\$3 or \$4CVD) with	US-PGPUB	
1	1	(pattern\$3 or nonuniform\$3 or (non adj		
		uniform\$3) or selecti\$6))) and (((427/552,553,555,558).CCLS.)		
		((427/226).CCLS.)		
		(((427/248.1,255.18,255.23) or	1	
		((\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\		
		((427/258, 259, 261, 264, 265, 270, 271).CCLS.)		
		((423/348,349).CCLS.) ((117/88,95).CCLS.))	1	
] -	1680	((Si or silicon) adj (coat\$3 or film or	USPAT;	2003/11/04 13:03
		layer or deposit\$3 or \$4CVD) with	US-PGPUB	2003/11/04 13:03
		(pattern\$3 or nonuniform\$3 or (non adj	""	
		uniform\$3) or selecti\$6) with (\$4CVD or	1]
		(vapor\$9)))		
-	37		USPAT;	2003/11/04 13:08
		layer or deposit\$3 or \$4CVD) with	US-PGPUB	
		(pattern\$3 or nonuniform\$3 or (non adj		
		uniform\$3) or selecti\$6) with (\$4CVD or	İ	!
	1	(vapor\$9)))) and		
		(((427/552,553,555,558).CCLS.)		
		((427/226).CCLS.)		[
		(((427/248.1,255.18,255.23) or (438/503,507)).CCLS.)		
		((427/258,259,261,264,265,270,271).CCLS.)	1	
		((423/348,349).CCLS.) ((117/88,95).CCLS.))		
-	589		USPAT;	2003/11/04 13:14
	555	\$4CVD) near2 (Si or silicon))	US-PGPUB;	2003/11/04 13:14
]	(or or original)	EPO; JPO;	
	1		DERWENT;	
			IBM TDB	[
-	20	((selective near2 (coat\$3 or deposit\$3 or	USPAT;	2003/11/04 13:32
	ļ i	\$4CVD) near2 (Si or silicon))) and (SAM or	US-PGPUB;	=====================================
	[monolayer or (self adj assemb\$7) or (mono	EPO; JPO;	
		adj layer))	DERWENT;	
	[IBM TDB	
-	106	(selective near2 (coat\$3 or deposit\$3 or	USPĀT;	2003/11/04 13:30
		\$4CVD) near2 (Si or silicon)) same	US-PGPUB;	
		pattern\$3	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	103	((selective near2 (coat\$3 or deposit\$3 or	USPĀT;	2003/11/04 13:15
1		\$4CVD) near2 (Si or silicon)) same	US-PGPUB;	
		pattern\$3) not (((selective near2 (coat\$3	EPO; JPO;	
		or deposit\$3 or \$4CVD) near2 (Si or silicon))) and (SAM or monolayor or (sale	DERWENT;	
1		silicon))) and (SAM or monolayer or (self adj assemb\$7) or (mono adj layer)))	IBM_TDB	
_	103		EDO: TEC	2002/14/24 15 5
	103	<pre>(selective near2 (coat\$3 or deposit\$3 or \$4CVD) near2 (Si or silicon))</pre>	EPO; JPO;	2003/11/04 13:32
]		vacon, nears (or or silicon))	DERWENT;	
L	Li		IBM TDB	

_	29		EPO; JPO;	2003/11/04 13:37
		\$4CVD) near2 (Si or silicon))) and (SAM	DERWENT;	
	1	or monolayer or (self adj assemb\$7) or	IBM_TDB	
		(mono adj layer) or inactiv\$5 or mask\$3 or		
		deactiv\$5 or (in adj activ\$5) or (de adj		
	1.2	activ\$5))	EDO. IDO.	2003/11/04 13:38
-	13	(selective near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) same (SAM or	EPO; JPO; DERWENT;	2003/11/04 13:36
		monolayer or (self adj assemb\$7) or (mono	IBM_TDB	
		adj laver))	100	
l _	109		USPAT;	2003/11/04 13:45
		or deposit\$3 or \$4CVD)) same (SAM or	US-PGPUB	
		monolayer or (self adj assemb\$7) or (mono		
}		adj layer))		
-	7	"9 ⁷ 074 ² 9"	EPO; JPO;	2003/11/04 13:45
			DERWENT	
-	37	1 ' '	EPO; JPO;	2003/11/04 13:50
		layer or deposit\$3 or \$4CVD)) and ((ring	DERWENT;	
ĺ		adj silane) or (cyclic adj silane) or	IBM_TDB	
		cyclosilane or cyclopentasilane or Si5H10		
		or "Si.sub.5 H.sub.10" or		
		"Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
		cyclopentasilane))		
_	141	1	USPAT;	2003/11/04 14:01
		layer or deposit\$3 or \$4CVD)) and ((ring	US-PGPUB	
		adj silane) or (cyclic adj silane) or		
		cyclosilane or cyclopentasilane or Si5H10		
		or "Si.sub.5 H.sub.10" or		
		"Si.sub.5H.sub.10" or (cyclo adj		
		pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6		,
		H.sub.12" or (silyl near2		
		cyclopentasilane))		
_	14		USPAT;	2003/11/04 13:52
	**	layer or deposit\$3 or \$4CVD)) and ((ring	US-PGPUB	2003, 11, 01 13.32
		adj silane) or (cyclic adj silane) or		
		cyclosilane or cyclopentasilane or Si5H10		
		or "Si.sub.5 H.sub.10" or		
		"Si.sub.5H.sub.10" or (cyclo adj		
		pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
1		H.sub.12" or (silyl near2		
		cyclopentasilane))) and		
		(((427/552,553,555,558).CCLS.) ((427/226).CCLS.)	1	
		((427/228).ccls.) (((427/248.1,255.18,255.23) or		
		(438/503,507)).CCLS.)		
1	1	((427/258,259,261,264,265,270,271).CCLS.)		
L	1	((423/348,349).CCLS.) ((117/88,95).CCLS.))		

-	127	(((silicon or Si) near2 (coat\$3 or film or	USPAT;	2003/11/04 13:52
		layer or deposit\$3 or \$4CVD)) and ((ring	US-PGPUB	
		adj silane) or (cyclic adj silane) or		
		cyclosilane or cyclopentasilane or Si5H10	į	
		or "Si.sub.5 H.sub.10" or		
		"Si.sub.5H.sub.10" or (cyclo adj		
		pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
	ľ	or "Si.sub.6H.sub.12" or "Si.sub.6		1
		H.sub.12" or (silyl near2		
		<pre>cyclopentasilane))) not ((((silicon or Si)</pre>		
		near2 (coat\$3 or film or layer or		
		deposit\$3 or \$4CVD)) and ((ring adj		
		silane) or (cyclic adj silane) or		
		cyclosilane or cyclopentasilane or Si5H1O		
		or "Si.sub.5 H.sub.10" or		
}		"Si.sub.5H.sub.10" or (cyclo adj		i .
1		pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
]		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
		cyclopentasilane))) and		
		(((427/552,553,555,558).CCLS.)		1
1		((427/226).CCLS.)		1
		(((427/248.1,255.18,255.23) or		
		(438/503,507)).CCLS.)		
i .		((427/258,259,261,264,265,270,271).CCLS.)		
l i		((423/348,349).CCLS.)		
		((117/88,95).CCLS.)))		.
-	2	((((silicon or Si) near2 (coat\$3 or film	USPAT;	2003/11/04 13:54
		or layer or deposit\$3 or \$4CVD)) and	US-PGPUB	
		((ring adj silane) or (cyclic adj silane)		j
		or cyclosilane or cyclopentasilane or		
		Si5H10 or "Si.sub.5 H.sub.10" or		
		"Si.sub.5H.sub.10" or (cyclo adj		1
	İ	pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
i		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		*
		cyclopentasilane))) not (((silicon or Si)		
ı	1	near2 (coat\$3 or film or layer or		
, <u>l</u>	l	deposit\$3 or \$4CVD)) and ((ring adj		
, 1		silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10	İ	
, [or "Si.sub.5 H.sub.10" or		
		"Si.sub.5H.sub.10" or (cyclo adj		
ĺ		pentasilane) or (cyclo adj penta adj		
į		silane) or silylcyclopentasilane or Si6H12		
, ,		or "Si.sub.6H.sub.12" or "Si.sub.6		
İ		H.sub.12" or (silyl near2		
l		cyclopentasilane))) and		1
ļ		(((427/552,553,555,558).CCLs.)		İ
ĺ		((427/226).CCLS.)		
		(((427/248.1,255.18,255.23) or		1
ļ		(438/503,507)).CCLS.)		
		((427/258,259,261,264,265,270,271).CCLS.)	1	
	[((423/348,349).CCLS.)		
		((117/88,95).CCLS.)))) and ((monolayer or		
	1	(mono adj layer) or SAM or (self adj		
ļ		assembl\$3)))		

-	125	((((silicon or Si) near2 (coat\$3 or film	USPAT;	2003/11/04 13:54
		or layer or deposit\$3 or \$4CVD)) and	US-PGPUB	
		((ring adj silane) or (cyclic adj silane)		
		or cyclosilane or cyclopentasilane or		
		Si5H10 or "Si.sub.5 H.sub.10" or		
		"Si.sub.5H.sub.10" or (cyclo adj		
		pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		l i
į		cyclopentasilane))) not (((silicon or Si)		
į .		near2 (coat\$3 or film or layer or	}	
		· · · · · · · · · · · · · · · · · · ·		
1		deposit\$3 or \$4CVD)) and ((ring adj		
		silane) or (cyclic adj silane) or		
		cyclosilane or cyclopentasilane or Si5H10		
		or "Si.sub.5 H.sub.10" or		
		"Si.sub.5H.sub.10" or (cyclo adj		
		pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
		cyclopentasilane))) and		
		(((427/552,553,555,558).CCLS.)]
		((427/226).CCLS.)]
		(((427/248.1,255.18,255.23) or		•
		(438/503,507)).CCLS.)		
		((427/258,259,261,264,265,270,271).CCLS.)		
, ,		((423/348,349).CCLS.)		
		((117/88,95).CCLS.)))) not ((((silicon or		
ļ		Si) near2 (coat\$3 or film or layer or		1
1		deposit\$3 or \$4CVD)) and ((ring adj		1
		silane) or (cyclic adj silane) or		
		cyclosilane or cyclopentasilane or Si5H10		
		or "Si.sub.5 H.sub.10" or		
		"Si.sub.5H.sub.10" or (cyclo adj		
		pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		ii.
		cyclopentasilane))) not ((((silicon or Si)		1
		near2 (coat\$3 or film or layer or		
		deposit\$3 or \$4CVD)) and ((ring adj		Į l
		silane) or (cyclic adj silane) or		<u> </u>
		cyclosilane or cyclopentasilane or Si5H10		
		or "Si.sub.5 H.sub.10" or		
		"Si.sub.5H.sub.10" or (cyclo adj		
		pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
		cyclopentasilane))) and		
		(((427/552,553,555,558).CCLS.)		
		((427/226).CCLS.)		
		(((427/248.1,255.18,255.23) or		
		(438/503,507)).CCLS.)		
		((427/258,259,261,264,265,270,271).CCLS.)		
1		((423/348,349).CCLS.)		
		((117/88,95).CCLS.)))) and ((monolayer or		
		(mono adj layer) or SAM or (self adj		
		assembl\$3))))		
				ı

_	11	((silicon or Si) near4 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj pentasilane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane)) and (ink adj jet\$4 or inkjet\$4 or (bubble adj jet\$4) or	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/04 14:03
-	1	bubblejet\$4) ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane)) same (ink adj jet\$4 or inkjet\$4 or (bubble adj jet\$4) or bubblejet\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/04 14:21
-	2	6527847.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/04 14:13
-	401	(\$4CVD or (vapor adj deposit\$3)) same ((gas or inert or nitrogen or N2 or "N.sub.2") with parallel with (crucible or source or surface or vaporizer or blow\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/04 14:29
_	28	((\$4CVD or (vapor adj deposit\$3)) same ((gas or inert or nitrogen or N2 or "N.sub.2") with parallel with (crucible or source or surface or vaporizer or blow\$3))) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/04 14:24
-	67	((423/348,349).CCLS.) ((117/88,95).CCLS.)) (\$4CVD or (vapor adj deposit\$3)) same ((((inert or nonreactive or (non adj reactive) or noble) near2 gas\$4) or nitrogen or N2 or "N.sub.2" or hydrogen or H2 or "H.sub.2") with parallel with (crucible or source or surface or vaporizer or blow\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/04 14:31
	5	((\$4CVD or (vapor adj deposit\$3)) same ((((inert or nonreactive or (non adj reactive) or noble) near2 gas\$4) or nitrogen or N2 or "N.sub.2" or hydrogen or H2 or "H.sub.2") with parallel with (crucible or source or surface or vaporizer or blow\$3))) not (((\$4CVD or (vapor adj deposit\$3))) same ((gas or inert or nitrogen or N2 or "N.sub.2") with parallel with (crucible or source or surface or vaporizer or blow\$3))) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/04 14:31
		6541354.pn. or 6503570.pn. or 6527847.pn. or "20030229190" or "20020034585"	USPAT; US-PGPUB	2004/04/22 13:49

_	3	6715871.pn. or 6646662.pn. or 6599582.pn.	USPAT; US-PGPUB	2004/04/22 13:50
-	39	(Furusawa.in. or Miyashita.in. or	USPAT;	2004/04/22 14:03
		Yudasaka.in. or Shimoda.in. or	US-PGPUB;	
		Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj	EPO; JPO; DERWENT;	
		Epson).as.) and ((silicon or Si) near2	IBM TDB	
		(coat\$3 or film or layer or deposit\$3 or	_	
		\$4CVD)) and ((ring adj silane) or (cyclic adj (silane or silicon)) or cyclosilane or		
		cyclopentasilane or Si5H10 or "Si.sub.5		
		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo		
		adj pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2		0
		cyclopentasilane))		
-	34	, , , , , , , , , , , , , , , , , , , ,	USPAT;	2004/04/22 14:00
		Yudasaka.in. or Shimoda.in. or	US-PGPUB;	
		Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj	EPO; JPO; DERWENT;	
		Epson).as.) and ((silicon or Si) near2	IBM TDB	
		(coat\$3 or film or layer or deposit\$3 or		1
		\$4CVD)) and ((ring adj silane) or (cyclic		
		adj (silane or silicon)) or cyclosilane or cyclopentasilane or Si5H1O or "Si.sub.5		
		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo		
		adj pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2		
!		cyclopentasilane))) not (6541354.pn. or		!
		6503570.pn. or 6527847.pn. or		
_	14	"20030229190" or "20020034585")	,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,	0004/04/05
	14	(((Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or	USPAT; US-PGPUB;	2004/04/22 14:04
		Yokoyama.in. or Matsuki.in. or	EPO; JPO;	
		Takeuchi.in. or JSR.as. or (Seiko adj	DERWENT;	
		Epson).as.) and ((silicon or Si) near2	IBM_TDB	
		<pre>(coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic</pre>		
		adj (silane or silicon)) or cyclosilane or		
,		cyclopentasilane or Si5H10 or "Si.sub.5		
		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
		cyclopentasilane))) not (6541354.pn. or 6503570.pn. or 6527847.pn. or		
		"20030229190" or "20020034585")) and		
		(active with inactive with \$4CVD or (vapor		
_	1	near2 deposit\$3))	HODAM	0004/04/55
	1	(((Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or	USPAT; US-PGPUB;	2004/04/22 14:02
[Yokoyama.in. or Matsuki.in. or	EPO; JPO;	
		Takeuchi.in. or JSR.as. or (Seiko adj	DERWENT;	
		Epson).as.) and ((silicon or Si) near2	IBM_TDB	
		<pre>(coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic</pre>		
1		adj (silane or silicon)) or cyclosilane or		
		cyclopentasilane or Si5H10 or "Si.sub.5		
_		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj		
	ļ	silane) or silylcyclopentasilane or Si6H12		
	ĺ	or "Si.sub.6H.sub.12" or "Si.sub.6		İ
ļ		H.sub.12" or (silyl near2		
	-	cyclopentasilane))) not (6541354.pn. or 6503570.pn. or 6527847.pn. or		
		"20030229190" or "20020034585")) and		
		(active with inactive with (\$4CVD or		*
		(vapor near2 deposit\$3)))		

-	1	(((Furusawa.in. or Miyashita.in. or	USPAT;	2004/04/22 14:02
į	ļ	Yudasaka.in. or Shimoda.in. or	US-PGPUB;	
	†	Yokoyama.in. or Matsuki.in. or	EPO; JPO;	
		Takeuchi.in. or JSR.as. or (Seiko adj	DERWENT;	
		Epson).as.) and ((silicon or Si) near2	IBM_TDB	
		(coat\$3 or film or layer or deposit\$3 or]
		\$4CVD)) and ((ring adj silane) or (cyclic		
		adj (silane or silicon)) or cyclosilane or		1
ļ		cyclopentasilane or Si5H10 or "Si.sub.5		1
		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo		ļ
1		adj pentasilane) or (cyclo adj penta adj		
1		silane) or silylcyclopentasilane or Si6H12		
1		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
	1	cyclopentasilane))) not (6541354.pn. or]
		6503570.pn. or 6527847.pn. or		
		"20030229190" or "20020034585")) and		
		(active with inactive)		ĺ
_	26	(Furusawa.in. or Miyashita.in. or	USPAT;	2004/04/22 14:04
ļ		Yudasaka.in. or Shimoda.in. or	US-PGPUB;	
		Yokoyama.in. or Matsuki.in. or	EPO; JPO;	
		Takeuchi.in. or JSR.as. or (Seiko adj	DERWENT;	
		Epson).as.) and (((silicon or Si) near2	IBM TDB]
	1	(coat\$3 or film or layer or deposit\$3 or	12.1_122	
		\$4CVD)) same (\$4CVD or (vapor near2		
		deposit\$3))) and ((ring adj silane) or		
		(cyclic adj (silane or silicon)) or		
		cyclosilane or cyclopentasilane or Si5H10		
		or "Si.sub.5 H.sub.10" or		
		"Si.sub.5H.sub.10" or (cyclo adj]
	1	1		1
		pentasilane) or (cyclo adj penta adj		1
		silane) or silylcyclopentasilane or Si6H12		İ
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
	,	cyclopentasilane))		0004/04/00 4 4 00
-	4	, , , , , , , , , , , , , , , , , , , ,	USPAT;	2004/04/22 14:07
		Yudasaka.in. or Shimoda.in. or	US-PGPUB;	l
		Yokoyama.in. or Matsuki.in. or	EPO; JPO;	
		Takeuchi.in. or JSR.as. or (Seiko adj	DERWENT;	
		Epson).as.) and (active with inactive with	IBM_TDB	
		(\$4CVD or (vapor near2 deposit\$3)))		
-	3	,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,	USPAT;	2004/04/22 14:05
		Yudasaka.in. or Shimoda.in. or	US-PGPUB;	
		Yokoyama.in. or Matsuki.in. or	EPO; JPO;	
		Takeuchi.in. or JSR.as. or (Seiko adj	DERWENT;	
[Epson) as.) and (active with inactive with	IBM_TDB	
1		(\$4CVD or (vapor near2 deposit\$3)))) not		l i
		((((Furusawa.in. or Miyashita.in. or		
		Yudasaka.in. or Shimoda.in. or		
		Yokoyama.in. or Matsuki.in. or		
		Takeuchi.in. or JSR.as. or (Seiko adj		
		Epson).as.) and ((silicon or Si) near2		
		(coat\$3 or film or layer or deposit\$3 or		
]		\$4CVD)) and ((ring adj silane) or (cyclic		
]		adj (silane or silicon)) or cyclosilane or		
		cyclopentasilane or Si5H10 or "Si.sub.5		
		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo		
		adj pentasilane) or (cyclo adj penta adj		
]		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
		cyclopentasilane))) not (6541354.pn. or		
		6503570.pn. or 6527847.pn. or		
		"20030229190" or "20020034585")) and		
		(active with inactive))		
		//		L

-	2	(Furusawa.in. or Miyashita.in. or	USPAT;	2004/04/22 14:09
		Yudasaka.in. or Shimoda.in. or	US-PGPUB;	
	}	Yokoyama.in. or Matsuki.in. or	EPO; JPO;	
		Takeuchi.in. or JSR.as. or (Seiko adj	DERWENT;	
1		Epson).as.) and (active with inactive with	IBM TDB	
		(SAM or monolayer or (mono adj layer) or		
		monomolecular or (mono adj molecular) or		
		(self adj assemb\$5)))		
-	2		USPAT;	2004/04/22 14:11
		Yudasaka.in. or Shimoda.in. or	US-PGPUB;	
		Yokoyama.in. or Matsuki.in. or	EPO; JPO;	
	İ	Takeuchi.in. or JSR.as. or (Seiko adj	DERWENT;	
		Epson).as.) and ((SAM or monolayer or	IBM TDB	
		(mono adj layer) or monomolecular or (mono	12.1_100	
	1	adj molecular) or (self adj assemb\$5))		
		with (region or active or inactive or		
		pattern\$3 or (arrang\$4 near2 liquid) or		
İ				
		area) with (\$4CVD or (vapor near2		
l _	11	deposit(\$3)))	Habra	0004/04/55
	"		USPAT;	2004/04/22 14:11
		Yudasaka.in. or Shimoda.in. or	US-PGPUB;	1
]	Yokoyama.in. or Matsuki.in. or	EPO; JPO;	
	1	Takeuchi.in. or JSR.as. or (Seiko adj	DERWENT;	
		Epson).as.) and ((SAM or monolayer or	IBM_TDB	
		(mono adj layer) or monomolecular or (mono		
		adj molecular) or (self adj assemb\$5))	ļ	
		with (\$4CVD or (vapor near2 deposit\$3)))	Í	
-	9	((or mr) dbmrca.in. or	USPAT;	2004/04/22 14:11
		Yudasaka.in. or Shimoda.in. or	US-PGPUB;	
		Yokoyama.in. or Matsuki.in. or	EPO; JPO;	
	Ì	Takeuchi.in. or JSR.as. or (Seiko adj	DERWENT;	
		Epson).as.) and ((SAM or monolayer or	IBM TDB	
		(mono adj layer) or monomolecular or (mono		[
	l	adj molecular) or (self adj assemb\$5))		
		with (\$4CVD or (vapor near2 deposit\$3))))		
		not ((Furusawa.in. or Miyashita.in. or		J
	!	Yudasaka.in. or Shimoda.in. or		
	i	Yokoyama.in. or Matsuki.in. or		
		Takeuchi.in. or JSR.as. or (Seiko adj		
		Epson).as.) and ((SAM or monolayer or		
		(mono adj layer) or monomolecular or (mono]
i		adj molecular) or (self adj assemb\$5))		
		with (region or active or inactive or		
		pattern\$3 or (arrang\$4 near2 liquid) or		[]
		area) with (\$4CVD or (vapor near2		
_	1402	deposit(\$3))))		
	1492	(427/552,553,555,558).CCLS.	USPAT;	2004/04/22 15:34
<u>_</u>	2262	///27/240 1 255 12 255 223	US-PGPUB	
-	2363	((427/248.1,255.18,255.23) or	USPAT;	2004/04/22 15:35
		(438/503,507)).CCLS.	US-PGPUB	
-	2908	(427/258,259,261,264,265,270,271).CCLS.	USPAT;	2004/04/22 15:35
			US-PGPUB	
-	427	(423/348,349).CCLS.	USPAT;	2004/04/22 15:35
			US-PGPUB	
-	542	(117/88,95).CCLS.	USPAT;	2004/04/22 15:35
			US-PGPUB	100,00,22 10.00
-	7427	((427/552,553,555,558).CCLS.)	USPAT;	2004/04/22 15:36
		(((427/248.1,255.18,255.23) or	US-PGPUB	2004/04/22 13:30
		(438/503,507)).CCLS.)	OD LOEUD	
	i	((427/258, 259, 261, 264, 265, 270, 271).CCLS.)		
f		((423/348,349).CCLS.) ((117/88,95).CCLS.)		
		(,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,		

-	14	(((427/552,553,555,558).CCLS.)	USPAT;	2004/04/22 15:43
		(((427/248.1,255.18,255.23) or	US-PGPUB	
		(438/503,507)).CCLS.)	1	
1		((427/258,259,261,264,265,270,271).CCLS.)		
		((423/348,349).CCLS.) ((117/88,95).CCLS.))		
		and ((silicon or Si) near2 (coat\$3 or film		
		or layer or deposit\$3)) and ((ring adj		
		silane) or (cyclic adj silane) or	1	1
		cyclosilane or cyclopentasilane or Si5H10		
		or "Si.sub.5 H.sub.10" or		
ì	1	"Si.sub.5H.sub.10" or (cyclo adj]	
		pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
		cyclopentasilane))		
-	3	(((427/552,553,555,558).CCLS.) or	USPAT;	2004/04/22 15:39
		((427/258,259,261,264,265,270,271).CCLS.))	US-PGPUB	
		and ((ring adj silane) or (cyclic adj		
		silane) or cyclosilane or cyclopentasilane		
		or Si5H10 or "Si.sub.5 H.sub.10" or		
		"Si.sub.5H.sub.10" or (cyclo adj		
		pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6]
		H.sub.12" or (silyl near2		İ
		cyclopentasilane))		
-	34	((((427/248.1,255.18,255.23) or	USPAT;	2004/04/22 15:42
		(438/503,507)).CCLS.) and	US-PGPUB	
		((427/258,259,261,264,265,270,271).CCLS.))		
-	4862	(((427/552,553,555,558).CCLS.)	USPAT;	2004/04/22 15:42
		((427/226).CCLS.)	US-PGPUB	·
]	(((427/248.1,255.18,255.23) or		
		(438/503,507)).CCLS.)		
		((427/258, 259, 261, 264, 265, 270, 271).CCLS.)		
Ì		((423/348,349).CCLS.) ((117/88,95).CCLS.))		
		and (((silicon or Si) near2 (coat\$3 or		
		film or layer or deposit\$3 or \$4CVD or		
- 20		vaporiz\$5)) with (select\$7 or pattern\$3 or		
		nonuniform or (non adj uniform))) and		
		((monolayer or (mono adj layer) or		
		fluoroalkyl or fluorine or SAM or (self		
		adj assembl\$3) or fluoro\$12) with (mask\$3		
	ļ l	or inactiv\$5 or (in adj activ\$5) or		
1_		deactiv\$5 or (de adj activ\$5))))	MODE -	0000100
-	0	((((427/248.1,255.18,255.23) or	USPAT;	2004/04/22 15:43
1		(438/503,507)).CCLS.) and	US-PGPUB	l i
		((427/258,259,261,264,265,270,271).CCLS.))		
_	0	and ((423/348,349).CCLS.)		
]	((427/258, 259, 261, 264, 265, 270, 271).CCLS.)	USPAT;	2004/04/22 15:44
		and ((ring adj silane) or (cyclic adj	US-PGPUB	
		(silane or silicon)) or cyclosilane or		
1		cyclopentasilane or Si5H10 or "Si.sub.5		
]		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo		ĺ
		adj pentasilane) or (cyclo adj penta adj		
j		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
	1	cyclopentasilane))		I

				Y
-	14	(((427/552,553,555,558).CCLS.) or	USPAT;	2004/04/22 15:59
	-	(((427/248.1,255.18,255.23) or	US-PGPUB	
1		(438/503,507)).CCLS.) or		
	1	((117/88,95).CCLS.)) and ((ring adj		
		silane) or (cyclic adj (silane or		
		silicon)) or cyclosilane or]
		cyclopentasilane or Si5H10 or "Si.sub.5		
		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo		
		adj pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
		cyclopentasilane))		
_	34	(((427/248.1,255.18,255.23) or	USPAT;	2004/04/22 15:46
		(438/503,507)).CCLS.) and	US-PGPUB	
	1	((427/258,259,261,264,265,270,271).CCLS.)	00 10102	
_	123		USPAT;	2004/04/22 15:48
	123	(((427/248.1,255.18,255.23) or	US-PGPUB	2004/04/22 15:40
	i	((427/240.1,233.16,233.23) OI (438/503,507)).CCLS.)	OD TOLOD	
		((427/258,259,261,264,265,270,271).CCLS.)		1
		((423/348,349).CCLS.) ((117/88,95).CCLS.))		
				1
		and ((\$4CVD or (vapor near2 deposit\$3) or		
		vaporiz\$4) same ((pattern\$3 or active or		**
		inactive or region) near6 (liquid or		
		source or reagent or solution)))	WGDAE.	0004/04/00 25 55
-	7	((ring adj silane) or (cyclic adj	USPAT;	2004/04/22 16:05
		(silane or silicon)) or cyclosilane or	US-PGPUB	
		cyclopentasilane or Si5H10 or "Si.sub.5		
	ļ	H.sub.10" or "Si.sub.5H.sub.10" or (cyclo		
		adj pentasilane) or (cyclo adj penta adj		1
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6	•	
		H.sub.12" or (silyl near2		1
		cyclopentasilane)) same (pattern\$3 or		
		selectiv\$5)		*
-	30	((ring adj silane) or (cyclic adj	USPAT;	2004/04/22 16:04
		(silane or silicon)) or cyclosilane or	US-PGPUB	
		cyclopentasilane or Si5H10 or "Si.sub.5		
		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo		
		adj pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
		cyclopentasilane)) same (vapor\$9 or \$4CVD)		
-	9	((ring adj silane) or (cyclic adj	USPAT;	2004/04/23 08:31
		(silane or silicon)) or cyclosilane or	US-PGPUB	
		cyclopentasilane or Si5H10 or "Si.sub.5		
		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo		
		adj pentasilane) or (cyclo adj penta adj		I state
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
		cyclopentasilane)) same (SAM or monolayer]
		or monomolecular or (mono adj (layer or		
1		molecular)) or (self adj assemb\$5) or		
		mask\$3 or photomask\$3)		
_	103	(((ring adj silane) or (cyclic adj	HCDAT.	2004/04/23 08:32
	103	(silane or silicon)) or cyclosilane or	USPAT; US-PGPUB;	2004/04/23 08:32
		cyclopentasilane or Si5H10 or "Si.sub.5		
		Heigh 10" or "Gi gub Eu gub 10" am /1-	EPO; JPO;	
		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo	DERWENT;	
		adj pentasilane) or (cyclo adj penta adj	IBM_TDB	·
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
		<pre>cyclopentasilane)) same (pattern\$3 or select\$5))</pre>		
L		9616015011	L	

	1			
-	26	(((ring adj silane) or (cyclic adj	USPAT;	2004/04/23 08:36
		(silane or silicon)) or cyclosilane or	US-PGPUB;	
		cyclopentasilane or Si5H10 or "Si.sub.5	EPO; JPO;	
	1	H.sub.10" or "Si.sub.5H.sub.10" or (cyclo	DERWENT;	
		adj pentasilane) or (cyclo adj penta adj	IBM_TDB	1
		silane) or silylcyclopentasilane or Si6H12	-	
i		or "Si.sub.6H.sub.12" or "Si.sub.6		1
		H.sub.12" or (silyl near2	1	1
		cyclopentasilane)) same ((pattern\$3 or		
	1	select\$5) with (coat\$3 or film or layer or		
		deposit\$4 or \$4CVD or apply\$4)))		
1_	37	(((vapor near2 deposit\$3) or \$4CVD)	HCDAM.	2004/04/23 08:45
-	3'		USPAT;	2004/04/23 08:45
]		near3 (selecti\$6 or pattern\$5 or	US-PGPUB;	1
		nonuniform\$4 or (non adj uniform\$5))) and	EPO; JPO;	
Ì		((evaporat\$5 or vaporiz\$5) near3 (liquid	DERWENT;	1
		or reagent or solution or source or	IBM_TDB	
		crucible or material) near3 (pattern or	ŀ	
		select\$7))		
-	38549	(((vapor near2 deposit\$3) or \$4CVD or	USPAT;	2004/04/23 08:48
- 0		coat\$3 or apply\$3 or deposit\$4 or film or	US-PGPUB;	
		layer) near3 (selecti\$6 or pattern\$5 or	EPO; JPO;	
ļ		nonuniform\$4 or (non adj uniform\$5))) and	DERWENT;	
		((liquid or reagent or solution or source	IBM TDB	1
		or crucible or material) with (pattern or	TDE _ TDB	
				1
		select\$7 or region) with (mask\$3 or		1
		monolayer or SAM or (self adj assemb\$5) or		
		(mono adj layer) or monomolecular or (mono		
		adj molecular)))		
-	690	(((vapor near2 deposit\$3) or \$4CVD or	USPAT;	2004/04/23 08:50
		coat\$3 or apply\$3 or deposit\$4 or film or	US-PGPUB;	!
		layer) near3 (selecti\$6 or pattern\$5 or	EPO; JPO;	i
		nonuniform\$4 or (non adj uniform\$5))) and	DERWENT;	
		((liquid or reagent or solution or source	IBM TDB	1
		or crucible or material) with (pattern or		
		select\$7 or region) with (monolayer or SAM		
		or (self adj assemb\$5) or (mono adj layer)		
_	400	or monomolecular or (mono adj molecular)))	Hanra	2004/01/20 22 22
-	463	((((vapor near2 deposit\$3) or \$4CVD or	USPAT;	2004/04/23 08:53
		coat\$3 or apply\$3 or deposit\$4 or film or	US-PGPUB;	
		layer) near3 (selecti\$6 or pattern\$5 or	EPO; JPO;	
		nonuniform\$4 or (non adj uniform\$5))) and	DERWENT;	
		((liquid or reagent or solution or source	IBM TDB	
		or crucible or material) with (pattern or		
		select\$7 or region) with (monolayer or SAM		
		or (self adj assemb\$5) or (mono adj layer)		
		or monomolecular or (mono adj		
		molecular)))) and (evaporat\$5 or vaporiz\$5		
1		or \$4CVD or (vapor adj deposit\$3))		
_	74		Hebau.	2004/04/22 00:50
['4	(((vapor near2 deposit\$3) or \$4CVD or	USPAT;	2004/04/23 08:50
]		coat\$3 or apply\$3 or deposit\$4 or film or	US-PGPUB;	
		layer) near3 (selecti\$6 or pattern\$5 or	EPO; JPO;	
'		nonuniform\$4 or (non adj uniform\$5))) and	DERWENT;	
		((liquid or reagent or solution or source	IBM_TDB	
		or crucible or material) with (pattern or	_	
		select\$7 or region) with (monolayer or SAM		
		or (self adj assemb\$5) or (mono adj layer)		1
		or monomolecular or (mono adj molecular))		
1		with (mask\$3 or activ\$5 or inactiv\$5))		
i	17	((((vapor near2 deposit\$3) or \$4CVD or	USPAT;	2004/04/23 08:58
		coat\$3 or apply\$3 or deposit\$4 or film or	US-PGPUB;	2004,04/23 00.30
		layer) near3 (selecti\$6 or pattern\$5 or		
			EPO; JPO;	
ļ l		nonuniform\$4 or (non adj uniform\$5))) and	DERWENT;	
		((liquid or reagent or solution or source	IBM_TDB	
		or crucible or material) with (pattern or		
		select\$7 or region) with (monolayer or SAM		
	i	or (self adj assemb\$5) or (mono adj layer)		ļ
ļ		or monomolecular or (mono adj molecular))		[
<u> </u>		with (mask\$3 or activ\$5 or inactiv\$5)))		
		and ((evaporat\$5 or vaporiz\$5 or \$4CVD or		
1		(vapor adj deposit\$3)) with (selectiv\$5 or		
'				
	ì	pattern\$4 or region or portion))		!

	003	1 (CAGVD	T CONTA	10004/04/03 00 00
-	883	(\$4CVD or vaporiz\$5 or evaporat\$5 or (vapor adj deposit\$3)) near3 (crucible or	USPAT; US-PGPUB;	2004/04/23 09:00
		source or surface) near3 (pattern\$3 or	EPO; JPO;	
		(active near3 inactive))	DERWENT;	
		(doctive fields indoctive))	IBM TDB	
_	123	(\$4CVD or vaporiz\$5 or evaporat\$5 or	USPAT;	2004/04/23 09:09
		(vapor adj deposit\$3)) near3 (crucible or	US-PGPUB;	2001,01,20
		source) near3 (pattern\$3 or (active near3	EPO; JPO;	
		inactive))	DERWENT;	
			IBM TDB	
-	6	((\$4CVD or coat\$3 or film or layer or	USPAT;	2004/04/23 09:12
		deposit\$3) near3 (selectiv\$4 or	US-PGPUB;]
		pattern\$3)) and ((liquid or solution or	EPO; JPO;	1
		reagent) near6 (surface or substrate)	DERWENT;	İ
	615	near6 (active near4 inactive))	IBM_TDB	
-	615	((\$4CVD or coat\$3 or film or layer or	USPAT;	2004/04/23 09:13
		deposit\$3) near3 (selectiv\$4 or	US-PGPUB;	
		pattern\$3)) and (((liquid or solution or	EPO; JPO;]
		reagent) near6 (surface or substrate) near6 (pattern\$3 or select\$7)) same (\$4CVD	DERWENT;	
		or vapor\$9 or evaporat\$5))	IBM_TDB	
_	9407		USPAT;	2004/04/23 09:14
		((427/226).CCLS.)	US-PGPUB	2004/04/23 09:14
		(((427/248.1,255.18,255.23) or	OD TGLOD	
		(438/503,507)).CCLS.)		
		((427/258,259,261,264,265,270,271).CCLS.)		
		((423/348,349).CCLS.) ((117/88,95).CCLS.)		
-	39	· · · ·	USPAT;	2004/04/23 09:19
		deposit\$3) near3 (selectiv\$4 or	US-PGPUB	
		pattern\$3)) and (((liquid or solution or		
		reagent) near6 (surface or substrate)		
		near6 (pattern\$3 or select\$7)) same (\$4CVD		
		or vapor\$9 or evaporat\$5))) and		
		(((427/552,553,555,558).CCLS.)		
		((427/226).CCLS.)		
		(((427/248.1,255.18,255.23) or (438/503,507)).CCLS.)		
		((427/258,259,261,264,265,270,271).CCLS.)		
		((423/348,349).CCLS.) ((117/88,95).CCLS.)		
		((423/340,349).ccms.) ((117/60,93).ccms.)		
_	22		USPAT;	2004/04/23 09:20
İ		coat\$3 or apply\$3 or deposit\$4 or film or	US-PGPUB	2004/04/25 05.20
		layer) near3 (selecti\$6 or pattern\$5 or	00 10102	
		nonuniform\$4 or (non adj uniform\$5))) and		
		((liquid or reagent or solution or source		
1	1	or crucible or material) with (pattern or		
		select\$7 or region) with (monolayer or SAM		
		or (self adj assemb\$5) or (mono adj layer)		
		or monomolecular or (mono adj		
		molecular)))) and		
1	1	(((427/552,553,555,558).CCLS.)		
		((427/226).CCLS.) (((427/248.1,255.18,255.23) or		1
		((427/248.1,255.18,255.23) or (438/503,507)).CCLS.)		
		((427/258,259,261,264,265,270,271).CCLS.)		
		((423/348,349).CCLS.) ((117/88,95).CCLS.)		
))		
-	56	(((vapor adj deposit\$3) or \$4CVD) near2	USPAT;	2004/04/23 09:23
		(crucible or source or liquid or solution)	US-PGPUB;	
		<pre>near2 (selectiv\$5 or pattern\$3))</pre>	EPO; JPO;	
			DERWENT;	
	[IBM_TDB	
-	81	(((vapor adj deposit\$3) or \$4CVD) near3	USPAT;	2004/04/23 09:27
		(crucible or source or liquid or solution)	US-PGPUB;	.
	į l	near3 (mask\$3 or SAM or monolayer or	EPO; JPO;	
		monomolecular or (mono adj (layer or	DERWENT;	
	l	molecular)) or (self adj assembl\$4)))	IBM_TDB	

-	11	(((vapor adj deposit\$3) or \$4CVD) near3 (selectiv\$5 or pattern\$3)) and ((mask\$3 or inactiv\$5) near4 (SAM or monolayer or monomolecular or (mono adj (layer or	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/04/23 09:30
-	18	molecular)) or (self adj assembl\$4))) (((vapor adj deposit\$3) or \$4CVD or coat\$3 or film or deposit\$3 or layer or apply\$3) near3 (selectiv\$5 or pattern\$3)) and ((inactiv\$5) with (activ\$5) with (\$4CVD or (vapor near2 deposit\$4)))	IBM TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/04/23 09:33
_	40	(liquid or solution) near2 (vaporiz\$5 or evaporat\$4) near2 pattern\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/04/23 09:34
-	2	((liquid or solution) near2 (vaporiz\$5 or evaporat\$4) near2 pattern\$3) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/23 09:33
-	90	(liquid or solution) near3 (vaporiz\$5 or evaporat\$4) near3 pattern\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/04/23 09:34
_	2	((liquid or solution) near3 (vaporiz\$5 or evaporat\$4) near3 pattern\$3) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/23 09:34
-	88	((liquid or solution) near3 (vaporiz\$5 or evaporat\$4) near3 pattern\$3) not (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/23 10:26